

Satellite Workshop of XXXIV International Conference on
Phenomena in Ionized Gases (XXXIV ICPIG) &
10th International Conference on Reactive Plasmas (ICRP-10)

**New trends of plasma processes
for thin films and related materials
For the deep discussion on new trends
of plasma processes**

20 July, 2019

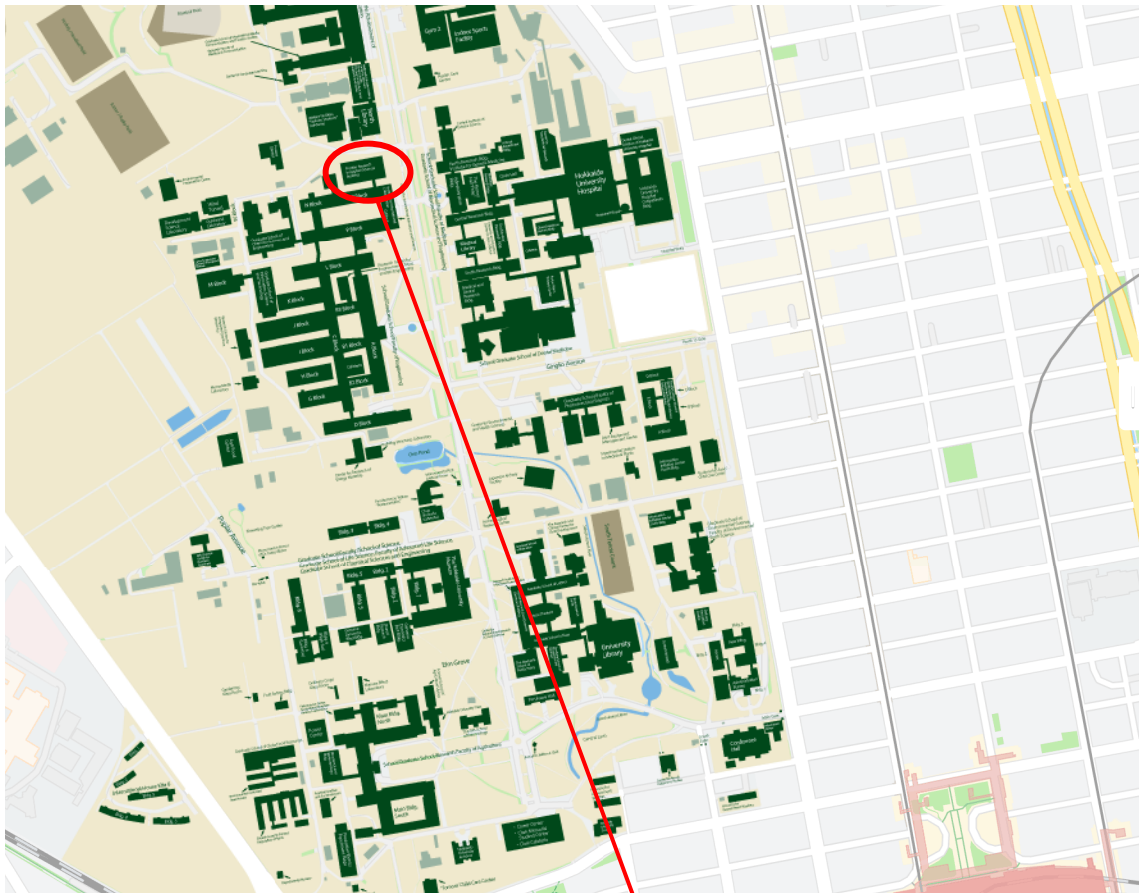


Seminar Room 1 on the 1st floor
Frontier Research in Applied Sciences Building
Hokkaido University, Sapporo, Hokkaido in Japan
<https://www.eng.hokudai.ac.jp/building/detail.php?area=2>
Sapporo Campus map
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**New trends of plasma processes for thin films and related materials for the deep
discussion on new trends of plasma processes**

8:30	Seminar Room 1 Open
8:50 - 9:00	Opening Remark
9:00 - 9:30	Seiji Samukawa , Tohoku University, Japan “State of the art of nano-processing of semiconductors”
9:30 - 10:00	Naho Itagaki , Kyushu University, Japan “Inverse Stranski-Krastanov growth: a method for growth of single crystalline films beyond lattice-matching condition”
10:00 - 10:30	Jón Tómas Guðmundsson , University of Iceland, Iceland “On the ionized flux fraction and ion recycling in high power impulse magnetron sputtering”
10:30 - 11:00	Break
11:30 - 12:00	Holger Kersten , University of Kiel, Germany “Novel diagnostics of sputtering phenomena”
12:00 - 12:30	Giichiro Uchida , Meijyo Univeristy, Japan “A search for novel materials for next-generation battery”
12:30 - 13:00	Masaharu Shiratani , Kyushu University, Japan “Nanoparticle inclusion: an old and new parameter for tuning film properties”
13:00 - 15:00	Break
15:00 - 18:00	Discussion on new trends of plasm processes

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